PCT

### PATENT COOPERATION TREATY

# **PCT**

REC'D 17 JAN 2006

INTERNATIONAL PRELIMINARY REPORT ON PATENTABIL TYPO

0

(Chapter II of the Patent Cooperation Treaty)

(PCT Artcle 36 and Rule 70)

Applicant's or agent's file reference ISPCT/168	FOR FURTHER ACTION	See Fo	rm PCT/IPEA/416			
International application No.  PCT/KR2004/002384  International filing date(day) 17 SEPTEMBER 200			date (day/month/year) TEMBER 2003 (26.09.2003)			
	PC) or national classification and IPC	.03/2001)				
pplicant KORNIC SYSTEMS CORI	?. et al					
Authority under Article 35 an	preliminary examination report, establed transmitted to the applicant according	to Article 36.	al Preliminary Examining			
<ol><li>This REPORT consists of a to</li></ol>	otal of 4 sheets, including	g this cover sheet.				
	ed by ANNEXES, comprising:					
a. (sent to the applicant and to the International Bureau) a total ofsheets, as follows:  sheets of the description, claims and/or drawings which have been amended and are the basis for this report and/or sheets containing rectifications authorized by this Authority (see Rule 70.16 and Section 607 of the Administrative Instructions).						
beyond the d Supplementa b. (sent to the Internat containing a sequen	supersede earlier sheets, but which this isclosure in the international application 1 Box.  ional Bureau only) a total of (indicate to the cellisting and/or tables related thereto, buence Listing (see Section 802 of the A.	n as filed, as indicated in type and number of electronic form only, a	ronic carrier(s)) as indicated in the Supplemental			
	ons relating to the following items:  of the report					
Box No. II Priorit	-					
L	stablishment of opinion with regard to 1	novelty, inventive step a	nd industrial applicability			
Box No. IV Lack of	of unity of invention					
Box No. V  Reasoned statement under Article 35(2) with regard to novelty, inventive step or industrial applicability; citations and explanations supporting such statement						
Box No. VI Certai	n documents cited					
Box No. VII Certain defects in the international application						
Box No. VIII Certain observations on the international application						
Date of submission of the demamo	Date o	of completion of this rep	ort			
27 MAY 2005	(27.05.2005)	10 JANUARY 2006	(10.01.2006)			
Name and mailing address of the Korean Intellectual P 920 Dunsan-dong, Se Republic of Korea		orized officer KIM, Sung Hee	AINE			
Facsimile No. 82-42-472-7140	Teler	hone No. 82-42-481-5	728			

## INTERNATIONAL PRELIMINARY REPORT ON PATENTABILITY

International application No.
PCT/KR2004/002384

Box No. I Basis of the report						
1.	otherv	regard to the language, this report is based on the international application in the language vise indicated under this item.  This report is based on translations from the original language into the following language which is the language of a translation furnished for the purposes of:  international search (under Rules 12.3 and 23.1(b))  publication of the international application (under Rule 12.4)  international preliminary examination (under Rules 55.2 and/or 55.3)				
2.	2. With regard to the elements of the international application, this report is based on (replacement sheets which have been furnished to the receiving Office in response to an invitation under Article 14 are referred to in this reort as "originally filed" and are not annexed to this report): the international application as originally filed/furnished					
		the description:  pages  pages*  pages*  received by this Authority on  pages*  received by this Authority on	as originally filed/furnished			
	ب	pages* received by this Authority on pages* received by this Authority on	as originally filed/furnished with any statment) under Article 19			
!			as originally filed/furnished			
3	з. 🗀	The amendments have resulted in the cancellation of:  the description, pages the claims, Nos.  the drawings, sheets the sequence listing (specify):  any table(s) related to sequence listing (specify):				
4	1.	This report has been established as if (some of) the amendments annexed to this report made, since they have been considered to go beyond the disclosure as filed, as indicated (Rule 70.2(c)).  the description, pages	ted in the Supplemental Box			
	* If ite	m 4 applies, some or all of those sheets may be marked "superseded."				

#### INTERNATIONAL PRELIMINARY REPORT ON PATENTABILITY

International application No.
PCT/KR2004/002384

Box No. V	Reasoned statement under Article 35(2) with regard to novelty, inventive step or industrial applicability;
	citations and explanations supporting such statement

1.	Statement			
	Novelty (N)	Claims	1-11	YES
	• • •	Claims		
	Inventive step (IS)	Claims	1-11	YES
İ	• • •	Claims		NO
	Industrial applicability (IA)	Claims	1-11	yes
	-	Claims		NO
ı				

- 2. Citations and explanations (Rule 70.7)
  - (1) Reference is made to the following documents:

D1: US 6,576,564 B2(Micron Technology, Inc.) 10 Jun. 2003 D2: US 6,255,197 B1(Jim Mitzel, Walnut Creek) 3 Jul. 2001 D3: US 5,464,499 A(Texas Instruments Inc.) 7 Nov. 1995 D4: US 5,571,749 A(Canon Kabushiki Kaisha) 5 Nov. 1996

D1 discloses a plasma processing system. The system comprises a remote plasma activation region for formation of active gas species; a transparent transfer tube coupled between the remote activation region and a semiconductor processing chamber; and a source of photo energy for maintaining activation of the active species during transfer from the remote plasma activation region to the processing chamber.

D2 discloses a hydrogen annealing method. The processing method includes providing a first gas including a hydrogen atom into a first chamber; igniting a plasma within the first chamber to provide a source of hydrogen atoms; passing the plasma downstream through a cavity to a second chamber disposed separately from the first chamber; and heating an object disposed within the second chamber.

D3 discloses a multi-electrode plasma processing system. The system includes a gas showerhead assembly, a radio-frequency chuck and a screen electrode. The screen electrode includes a base for positioning within the process chamber. The screen has numerous passageways to allow interaction of plasma and the process chamber walls.

D4 discloses a method and apparatus for forming deposited film. The apparatus comprises a vacuum chamber for forming a semiconductor layer; a vacuum chamber for forming a semiconductor having i-type conductivity on the semiconductor layer; heating and cooling means.

(See Supplemental Box)

#### INTERNATIONAL PRELIMINARY REPORT ON PATENTABILITY

International application No.

PCT/KR2004/002384

#### Supplemental Box

In case the space in any of the preceding boxes is not sufficient. Continuation of:

(Box No. V)

(2) Novelty and Inventive step

The subject matter of Claims 1-11 is about a plasma rapid thermal process apparatus in which a supply port of radical source is improved. The plasma rapid thermal process apparatus according to the present invention comprises a chamber including a supply port having an inside and outside tube and an exhaust port, a heat source for heating wafer, a gas supply module, a discharge tube and a microwave supply apparatus.

Although D1-D4 disclose a plasma processing system including transfer means coupled between the remote plasma activation region and a semiconductor processing chamber, none of the documents D1-D4, taken alone or in combination, discloses a supply port having an inside and outside tube defined in the invention. Furthermore, in the documents D1-D4 there are no suggestion leading a person skilled in the art towards the invention defined by the Claims 1-11.

Therefore, compared with the prior arts D1-D4, the subject matter of Claims 1-11 is considered to involve novelty and an inventive step under PCT Article 33(2) and 33(3).

(3) Industrial Applicability

The present invention is believed to be industrially applicable according to PCT Article 33(4).